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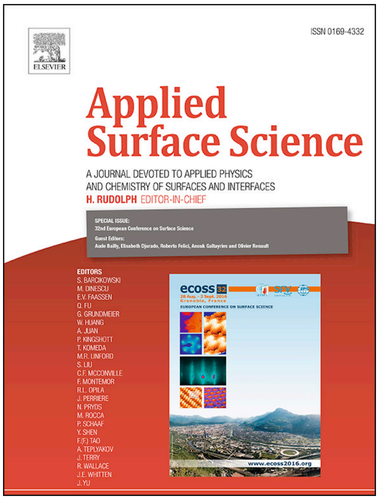

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# Selective etching of PDMS: etching as a negative tone resist

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Graphical abstract